

CLAIMS

1. A composition for forming a silicon·aluminum film, comprising a silicon compound and an aluminum compound.

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2. The composition for forming a silicon·aluminum film according to claim 1, wherein the silicon compound is at least one selected from the group consisting of compounds represented by the following formulas (1) to (4):



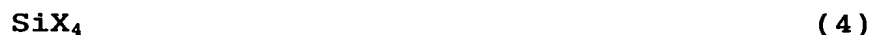
wherein X is a hydrogen atom, halogen atom or monovalent organic group and "a" is an integer of 2 or more.



15 wherein X is as defined in the above formula (1) and "b" is an integer of 3 or more.

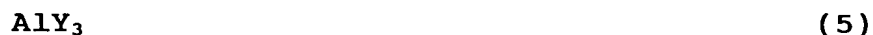


wherein X is as defined in the above formula (1) and "c" is an integer of 6 or more.



20 wherein X is as defined in the above formula (1).

3. The composition for forming a silicon·aluminum film according to claim 1, wherein the aluminum compound is at least one selected from the group consisting of a compound represented by the following formula (5) and a complex of an amine compound and aluminum hydride:



wherein Y is a hydrogen atom or monovalent organic group.

30 4. A method of forming a silicon·aluminum film, comprising the steps of forming a coating film of the composition for forming a silicon·aluminum film of any one of claims 1 to 3 on a substrate and treating the film with heat and/or light.

5. A silicon·aluminum film formed by the method of claim

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